

REMARKS

Claims 1-21 are now present in this case. Consideration of the application in view of the canceled claim and the following remarks is respectfully requested.

Election/Restriction

In the office action mailed April 30, 2002, the Examiner required restriction of prosecution to one of the following inventions: Group I drawn to a sequential method for integrated, in-situ modification of a substrate and subsequent atomic layer deposition of a thin film onto the substrate, and Group II, drawn to an apparatus/a single-module system for atomic layer deposition of a film onto a substrate.

Applicants hereby elect the invention of Group I drawn to a sequential method for integrated, in-situ modification of a substrate and subsequent atomic layer deposition of a thin film onto the substrate, and including claims 1-21 without traverse.

For purposes of satisfying the restriction requirement in the above-identified application, Applicants are removing from consideration the non-elected claim without traverse.

Respectfully submitted,

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By: 

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